

(Use several sheets if necessary)

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09/833,363

Boieriu et al.

04/12/2001

2878

PATENT DOCUMENTS

RECEIVED	
APR 10 1962	
10 2500 MAIL ROOM	

[illegible]

52		W. Kern and D.A. Puotinen, Cleaning solution based on hydrogen peroxide for use in silicon semiconductor technology, RCA Rev. 31, pp. 187-206 (1970)

DATE CONSIDERED

Form PTO-A820
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